

Reply under 37 C.F.R. 1.116
Expedited Procedure
Technology Center 2823

Confirmation No. 6408

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Meunier-Beillard *et al.* Examiner: Khiem Nguyen
Serial No.: 10/550,853 Group Art Unit: 2823
Filed: September 22, 2005 Docket No.: NL030357 US1
Title: METHOD OF EPITAXIAL DEPOSITION OF AN N-DOPED SILICON
LAYER

FINAL OFFICE ACTION RESPONSE

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Customer No.

65913

Dear Sir:

In response to the final Office Action dated September 17, 2007, please
reconsider the application in view of the following amendments and remarks.

A complete listing of the claims, to include any amendments presented therein,
begins on page 2 of this paper.

Remarks/Arguments follow on page 5.

**Authorization is provided to charge/credit Deposit Account 50-0996
(NXPS.265PA) any requisite fees/overages to enter this paper.**